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13.5nm, 25.4mm Dia, 5° AOI, EUV Spherical Mirror



TECHSPEC® Extreme Ultraviolet (EUV) Spherical Mirrors

Stock **#11-730** **20+ In Stock**

⊖ 1 ⊕ **\$6,034⁰⁰**

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General

Spherical Mirror **Type:**

Physical & Mechanical Properties

25.40 +0.00/-0.13 **Diameter (mm):**

6.35 ±0.25 **Thickness (mm):**

<3 RMS **Surface Roughness (□):**

Optical Properties

Metal/Semiconductor	Coating Type:
Mb/Si Multilayer Top Layer: Silicon	Coating:
$\lambda/10$ @ 632.8nm	Surface Flatness (P-V):
13.5	Design Wavelength DWL (nm):
250.00	Effective Focal Length EFL (mm):
Fused Silica (Corning 7980)	Substrate: <input type="checkbox"/>
5	Angle of Incidence (°):
$R_{\text{abs}} > 60\%$ @ 13.5nm	Coating Specification:
500.00	Radius R_1 (mm):
500.00	Radius of Curvature (mm):
0.50	Full Width-Half Max FWHM (nm):

Regulatory Compliance

View	Certificate of Conformance:
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Product Details

- Mb/Si Multilayer Coating on Super-Polished Substrates
- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Focusing Applications
- Narrow Pass Band for HHG Applications

Extreme Ultraviolet (EUV) Spherical Mirrors feature a multilayer Mb/Si coating providing greater than 60% reflection at 13.5nm. They are designed for a 5° angle of incidence and intended for focusing unpolarized EUV laser sources. A surface roughness of less than 3 \square RMS minimizes scatter. This is essential for EUV wavelengths which experience more scattering than longer wavelengths. EUV Spherical Mirrors have a very narrow pass band of approximately 0.5nm, ensuring that only the 13.5nm harmonic of interest is reflected in high harmonic generation (HHG) applications. [Typical applications](#) for EUV spherical mirrors include Coherent Diffractive Imaging (CDI), EUV imaging, and EUV nanomachining.

Note: Test data from each mirror's production run sample included.